

TOP SECRET 04842660

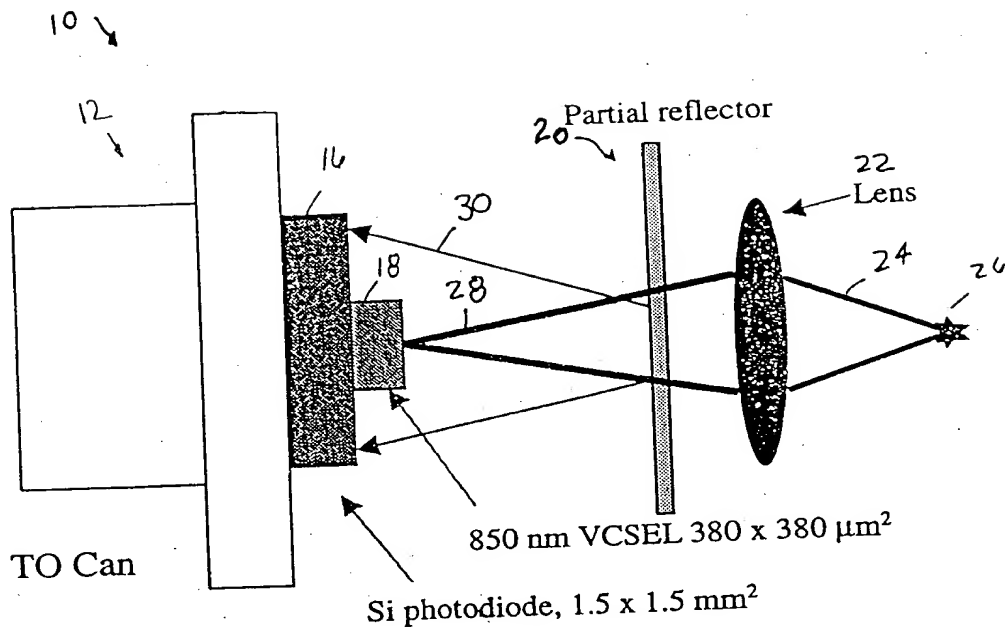


FIG. 1
PRIOR ART

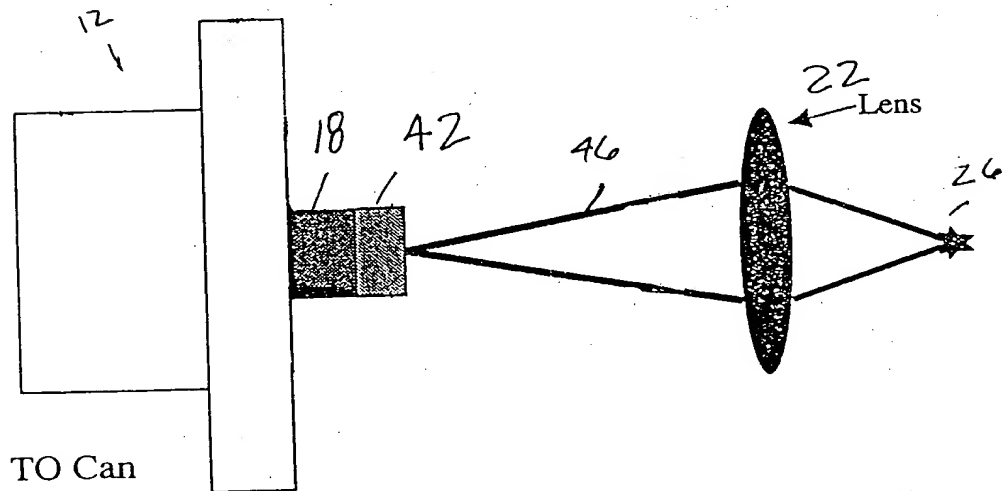


FIG. 2

50 ↘

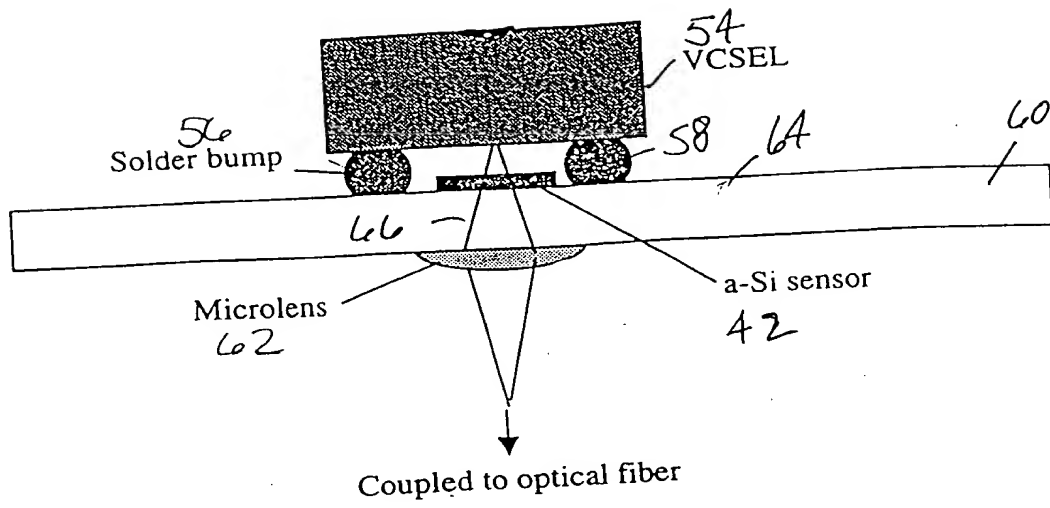


FIG. 3

70 ↘

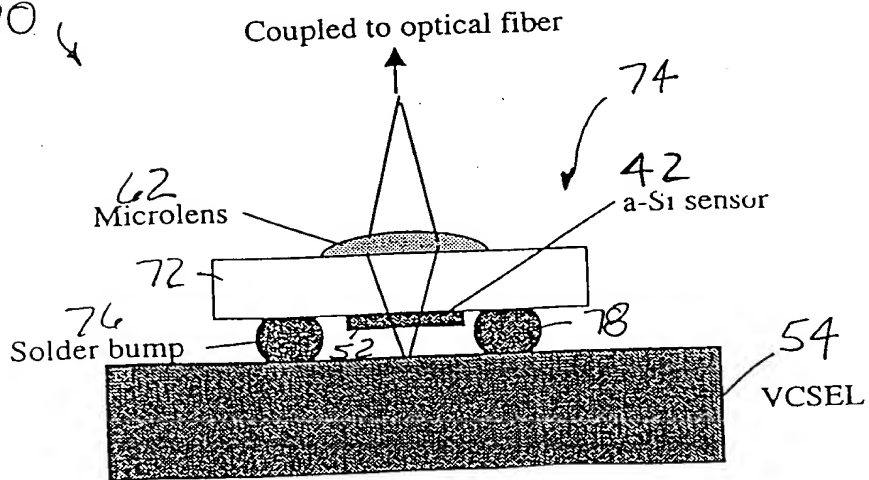


FIG. 4

09924340-080301

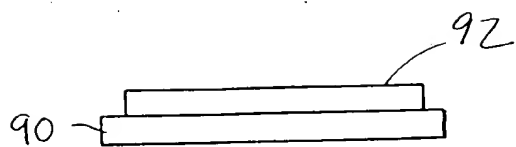


FIG. 5a

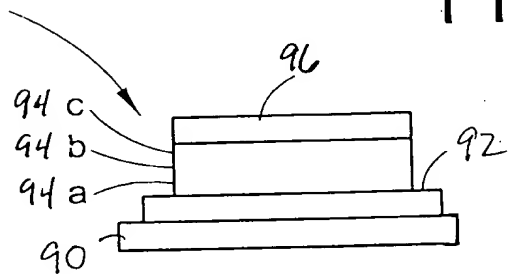


FIG. 5b

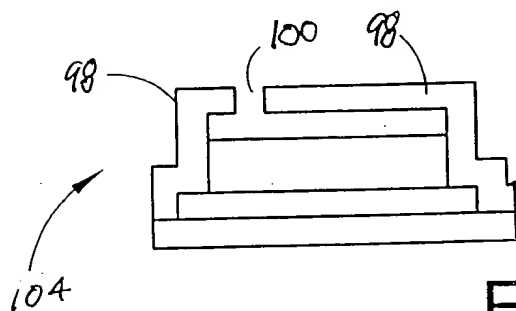


FIG. 5c

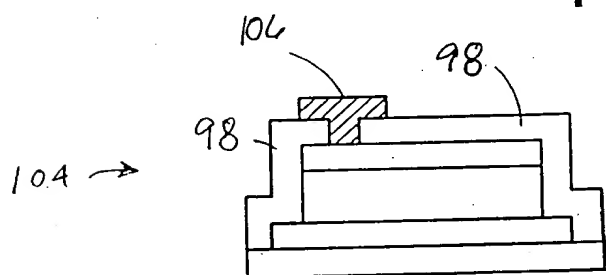


FIG. 5d

FIG. 5a

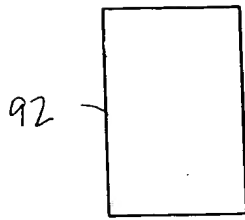


FIG. 6a

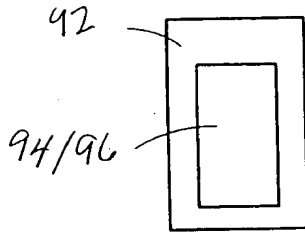


FIG. 6b

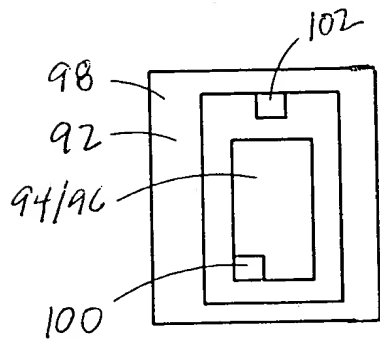


FIG. 6c

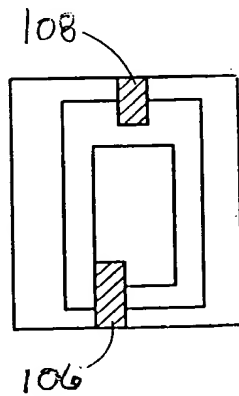


FIG. 6d

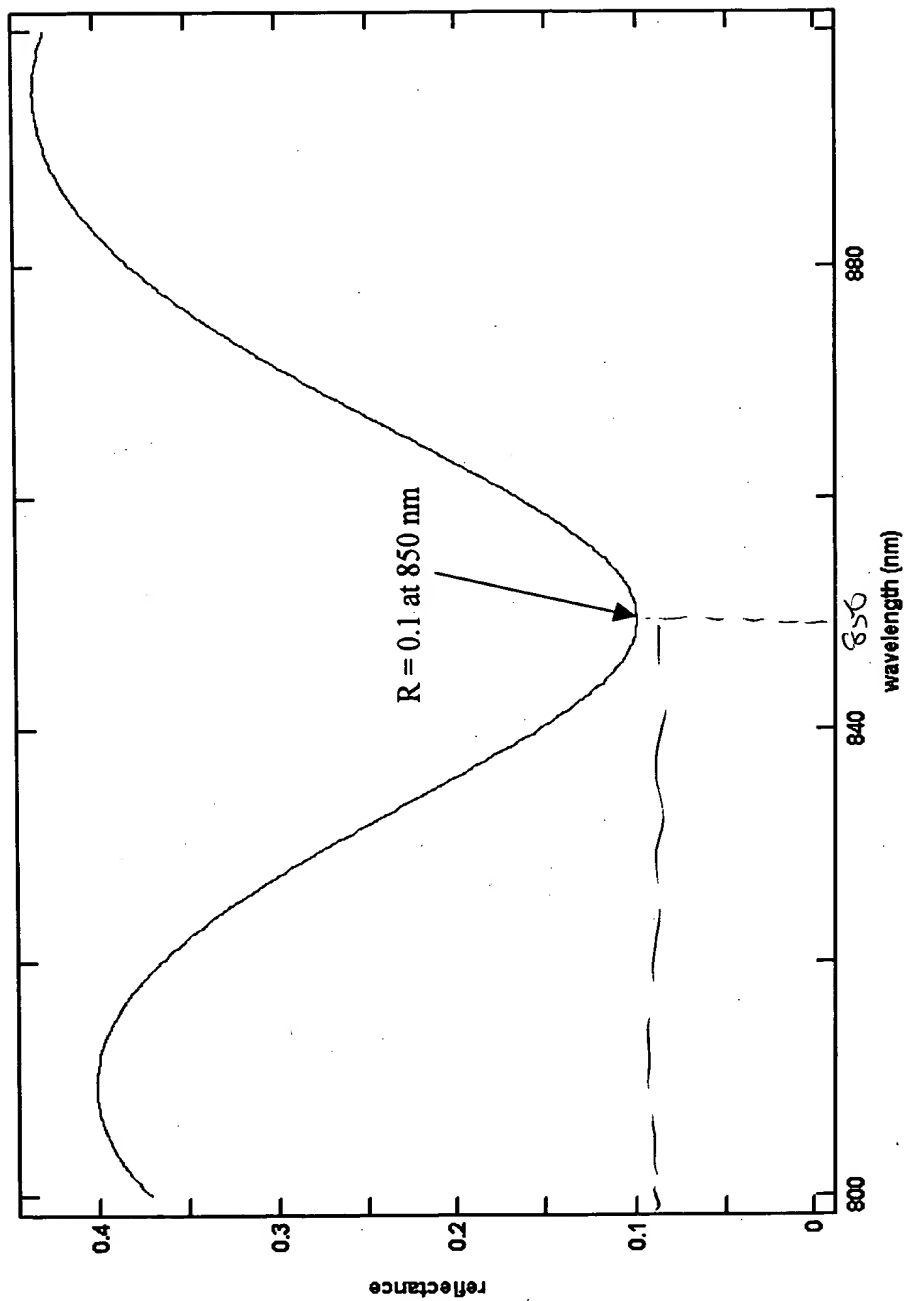


Figure 7

09924340-030301

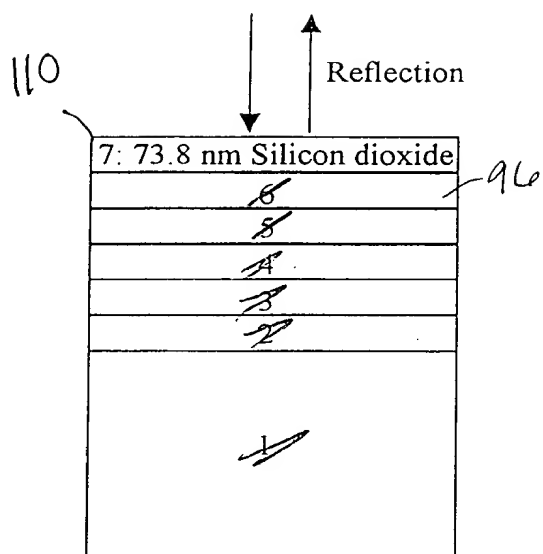


FIG. 8

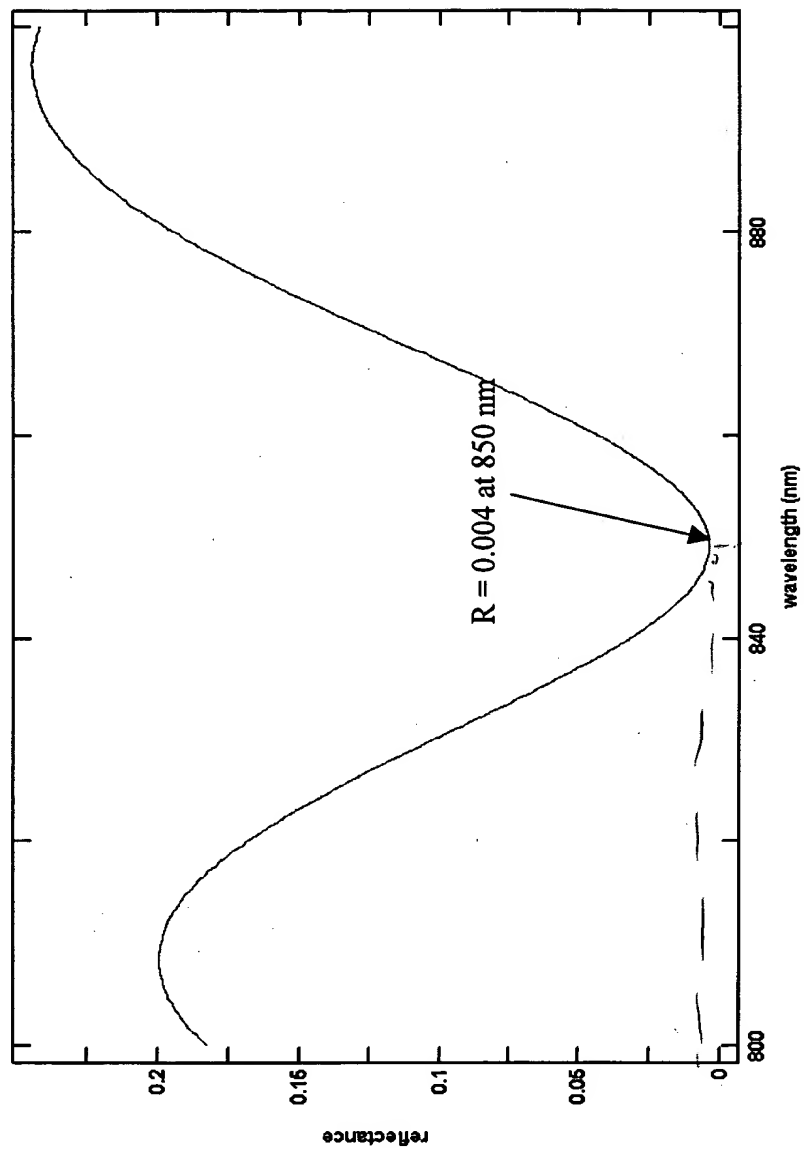


Figure 9

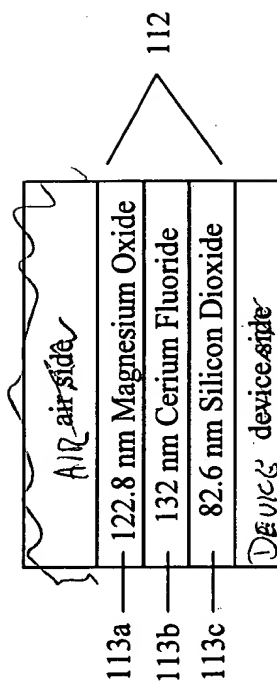


Figure 10

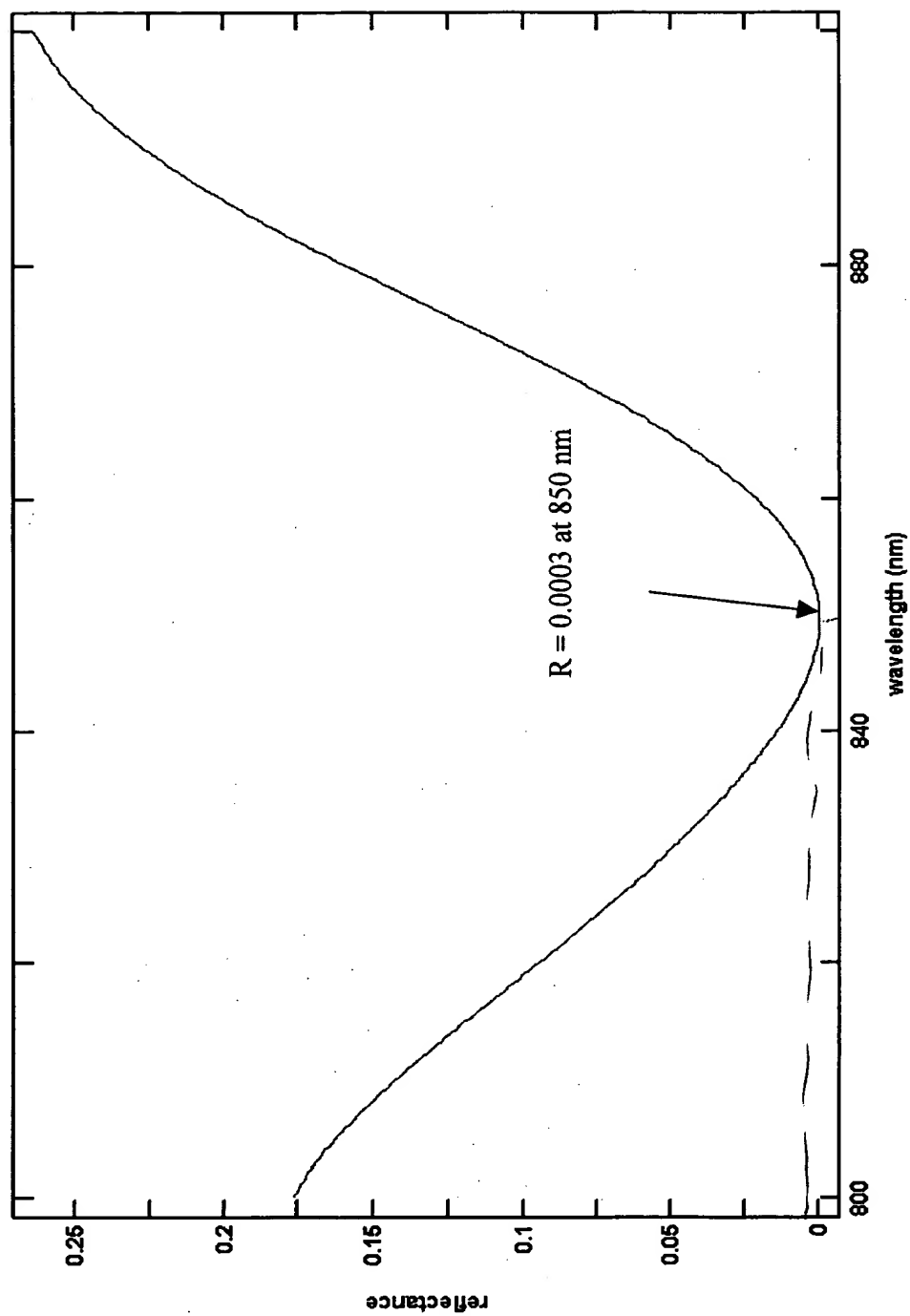


Figure 11

T08080" 04842660

X	X	X	X	X	Air	X	X	X	X
X	X	X	X	X	SiO ₂ (225.2 nm)	X	X	X	X
X	X	X	X	X	TiO ₂ (93.5 nm)	X	X	X	X
X	X	X	X	X	ITO (20 nm)	X	X	X	X
X	X	X	X	X	Si (707.7 nm)	X	X	X	X
X	X	X	X	X	ITO (10 nm)	X	X	X	X
X	X	X	X	X	TiO ₂ (87.2 nm)	X	X	X	X
X	X	X	X	X	glass substrate	X	X	X	X

12A

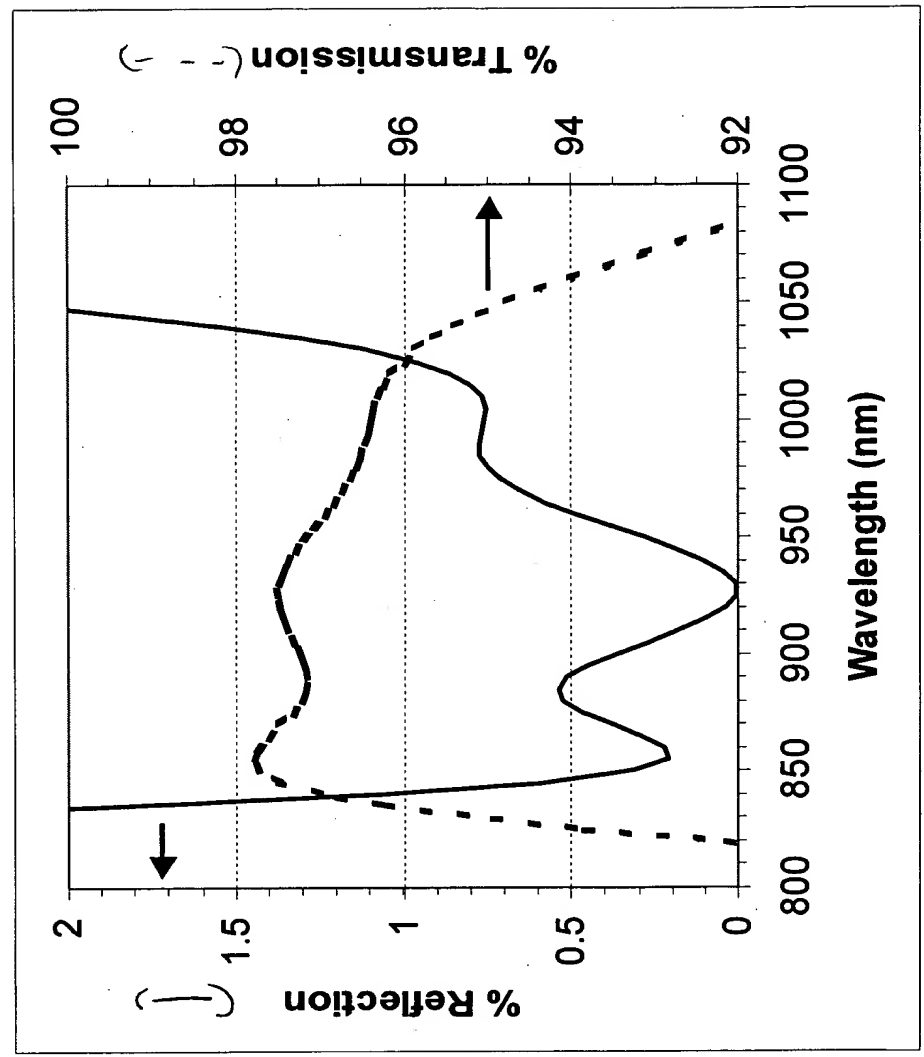


Figure 12B

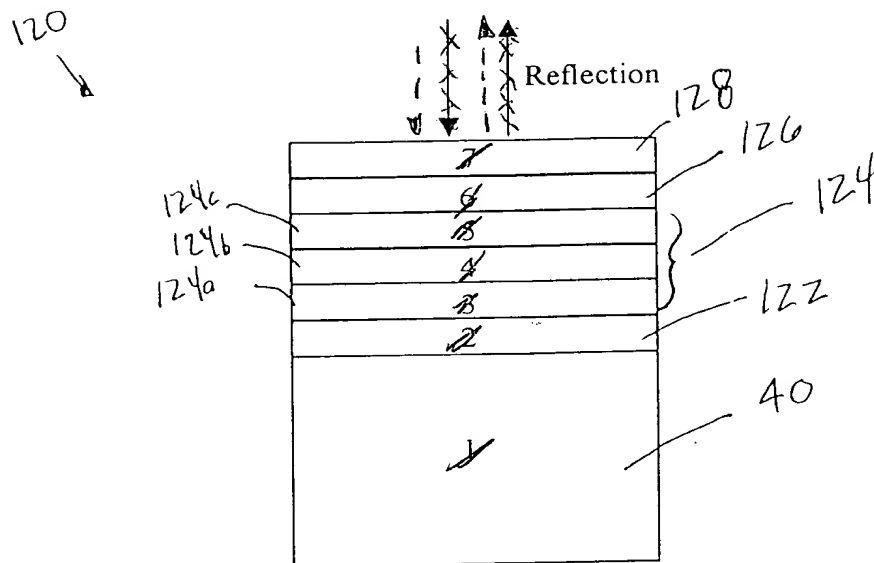


FIG. 13

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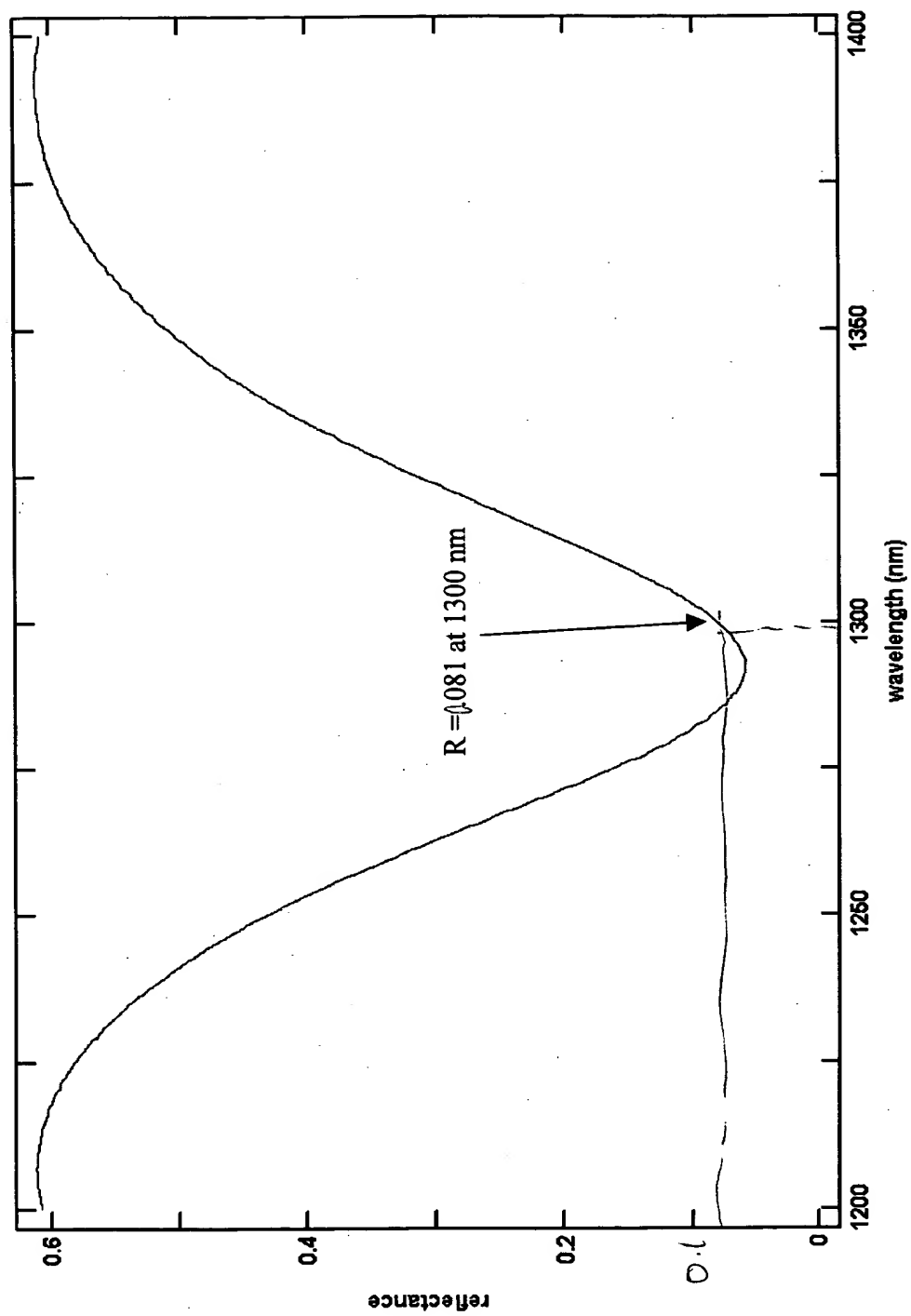


Figure 14

Air-side	
189 nm Magnesium Oxide	129
203.1 nm Cerium Fluoride	
108.3 nm Silicon Dioxide	
Device side	

Figure 15

T08080" 04842660

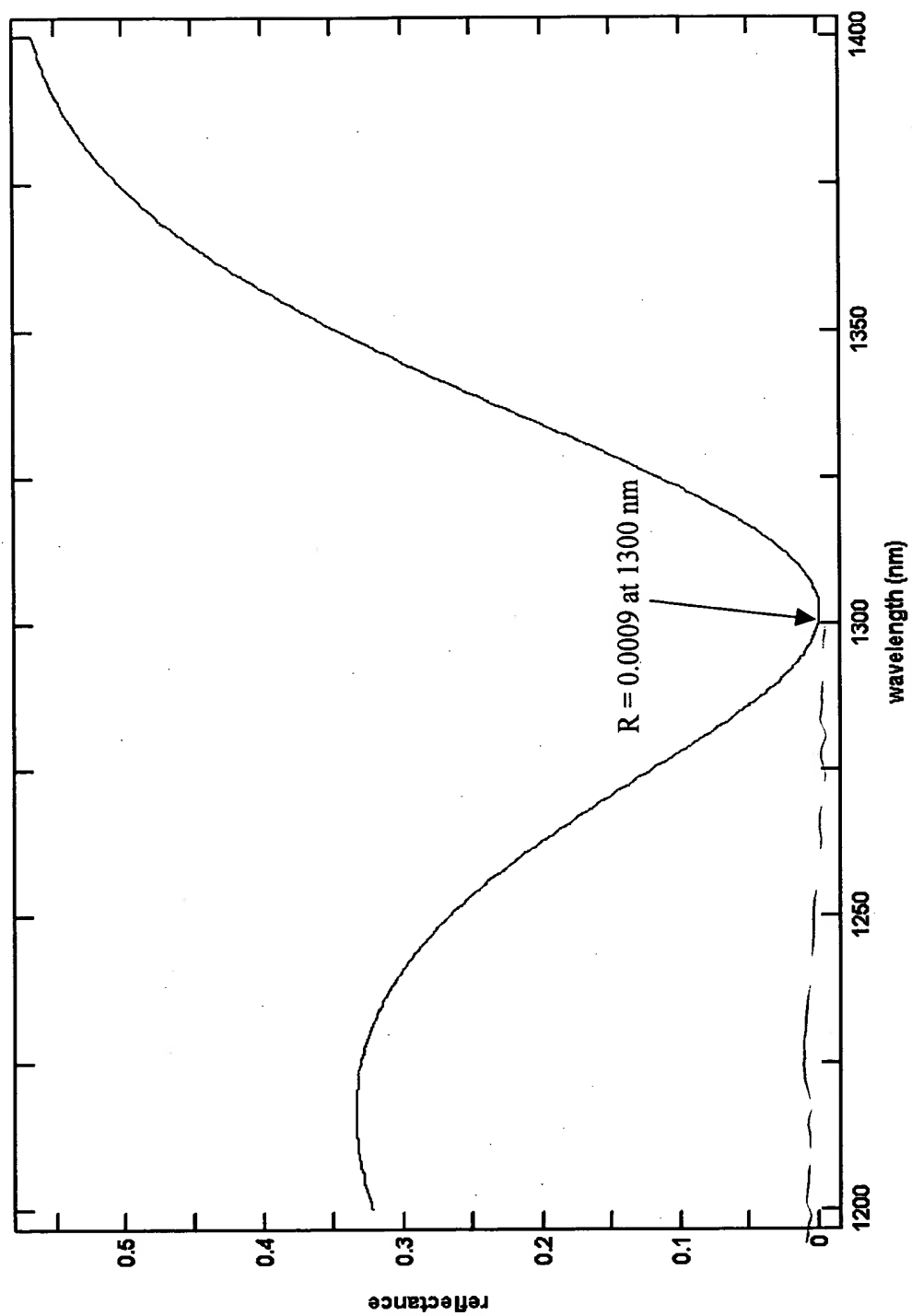


Figure 16

X	Air	X	X	X
X	SiO ₂	(274.6 nm)		
X	Si	(68.1 nm)		
X	96 — ITO	(20 nm)		
X	94 — Si	(663 nm)		
X	92 — ITO	10 nm		
X	Si	(141.8 nm)		
X	SiO ₂	(86.68 nm)		
X	Si	(35.48 nm)		
X	glass substrate			

17A

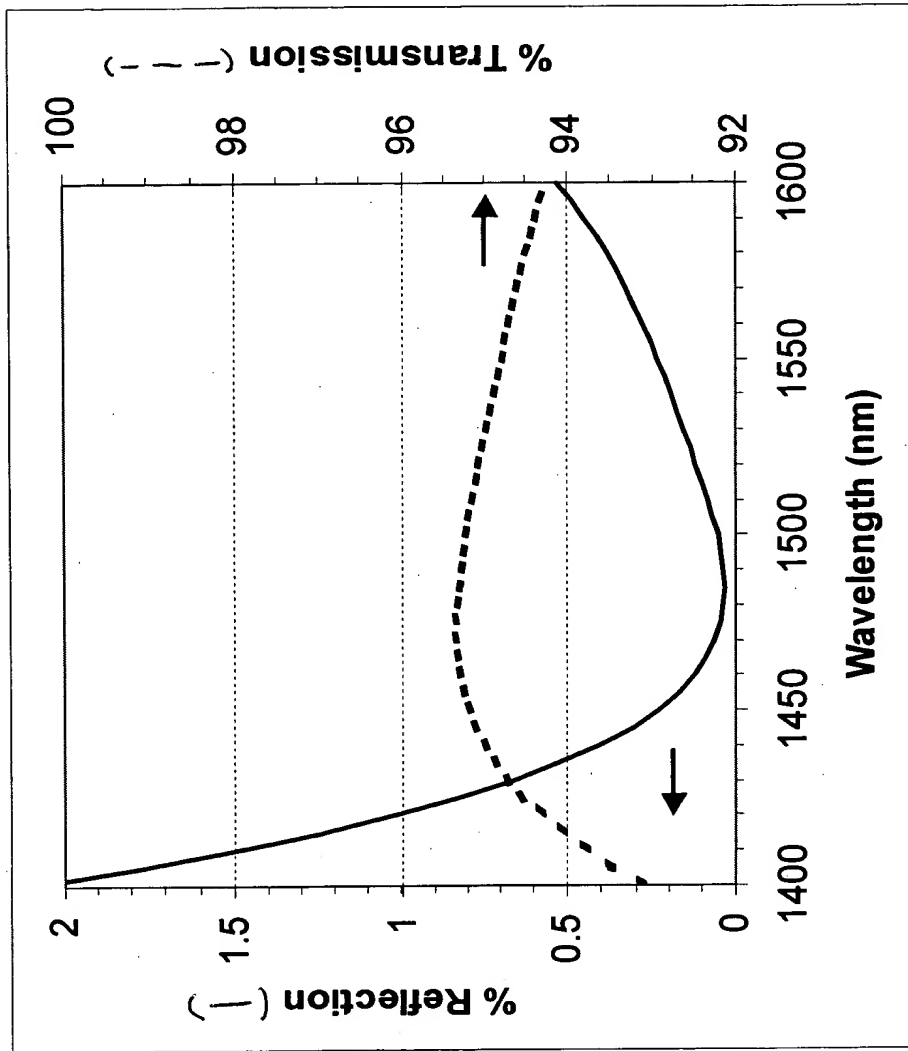


Figure 17B

X	X	Air	X	X
		SiO ₂ (154.8 nm)		
X		TiO ₂ (102.3 nm)		
X	96	ITO (20 nm)		
X	94	Si (601.5 nm)		
X	92	ITO (10 nm)		
X		TiO ₂ (158.1 nm)		
X	X	glass substrate	X	X

18A

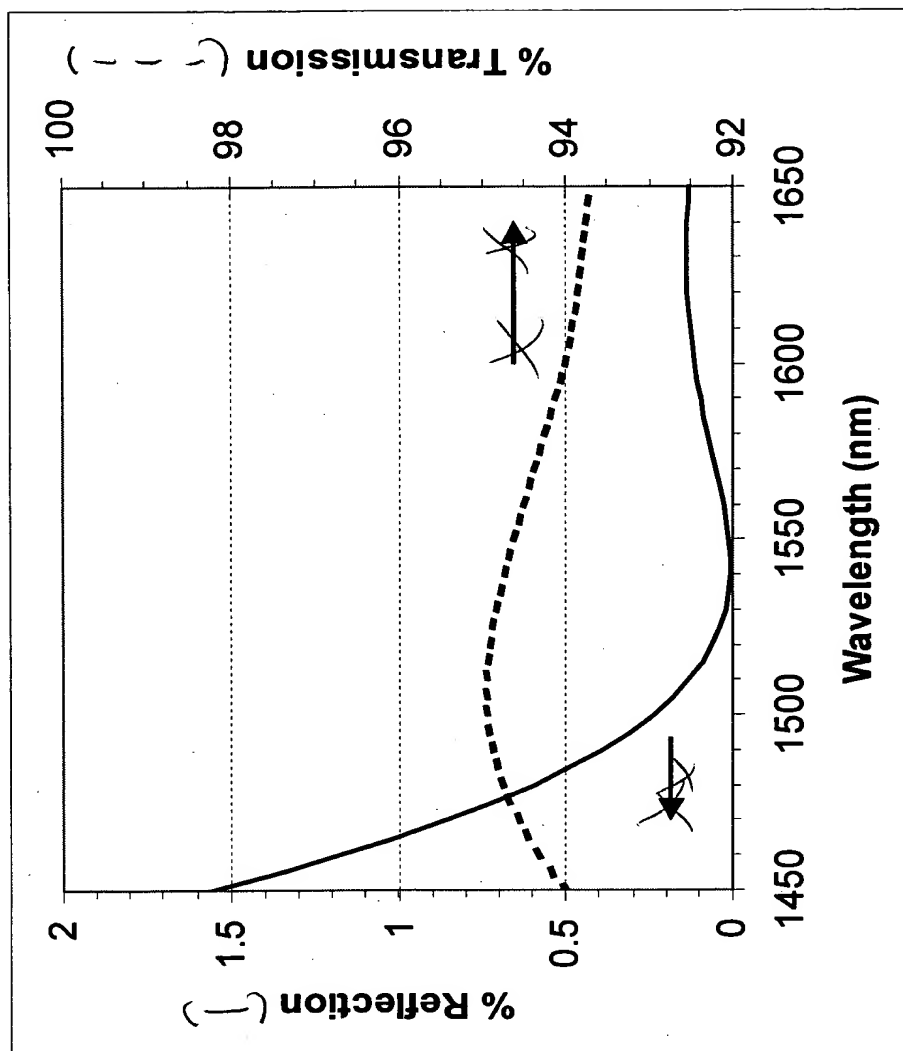


Figure 18B

X	Air	X	X	X	X
X	SiO₂	(181.2 nm)	X	X	X
X	TiO₂	(106.9 nm)	X	X	X
X	96-ITO	(10 nm)	X	X	X
X	94-Si	(569 nm)	X	X	X
X	92-ITO	(5 nm)	X	X	X
X	TiO₂	(158.3 nm)	X	X	X
X	glass substrate	X	X	X	X

19A

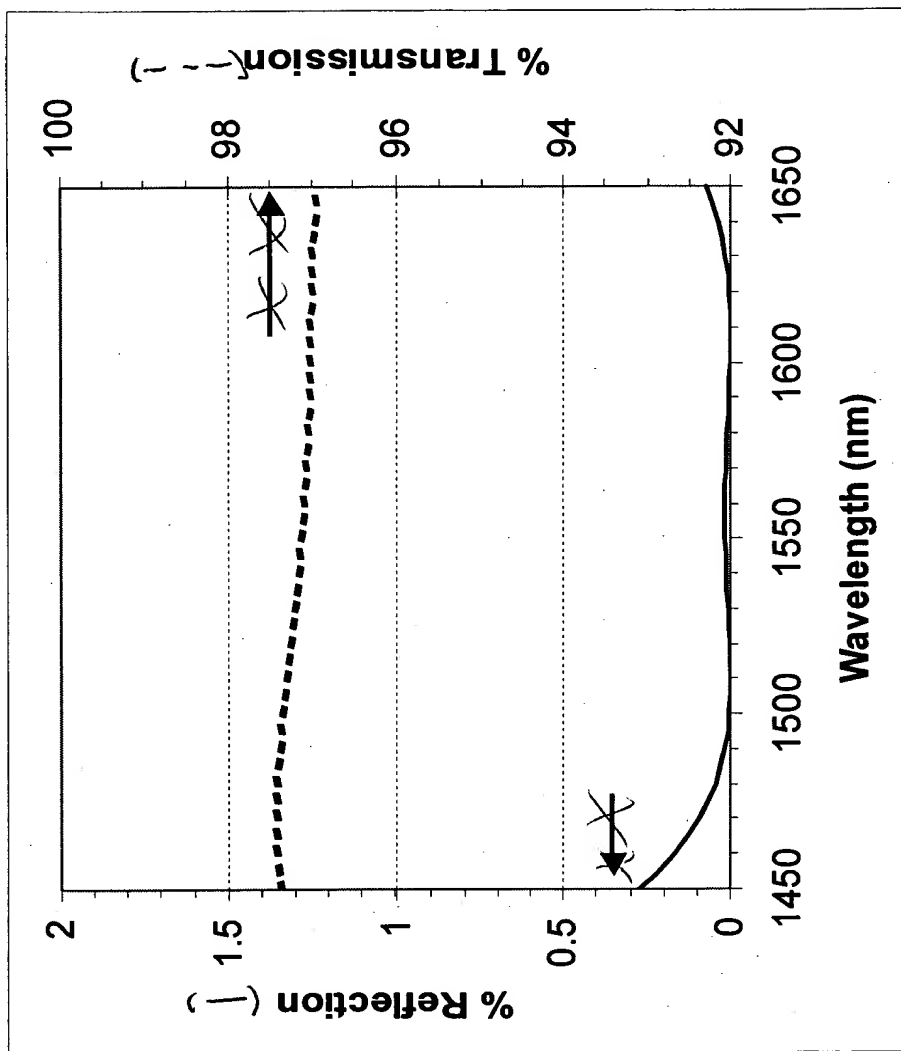


Figure 19B

09924840-030801

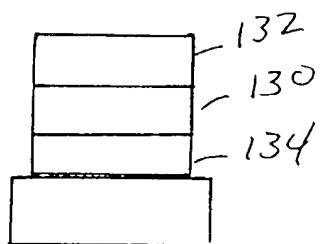


FIG. 20

09924840-080801

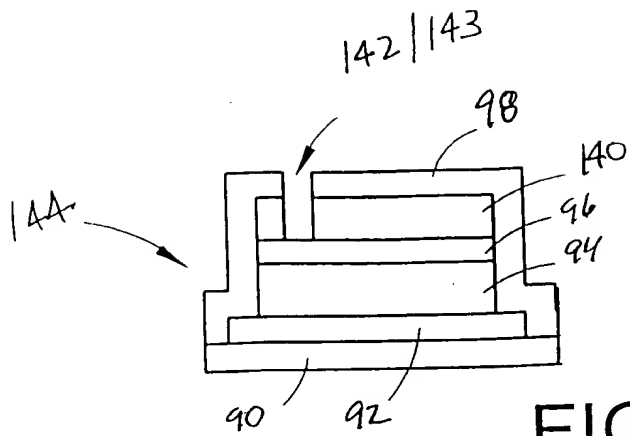


FIG. 21a

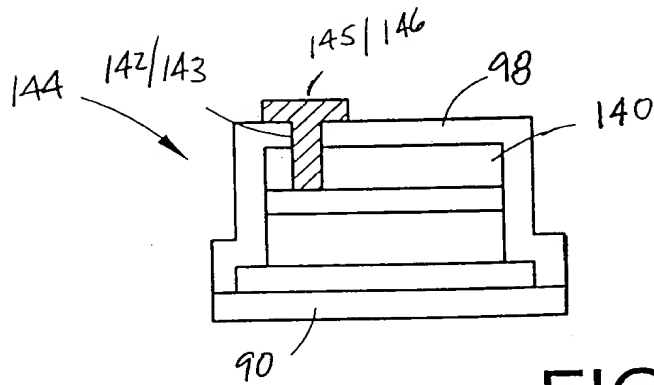


FIG. 21b

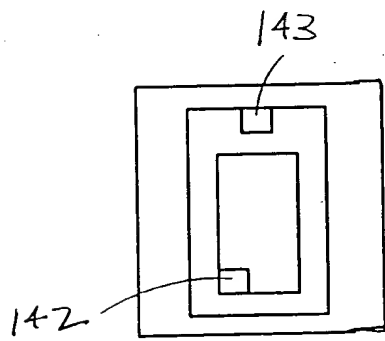


FIG. 22a

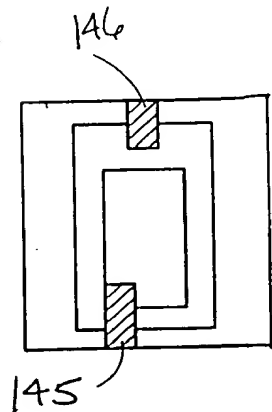
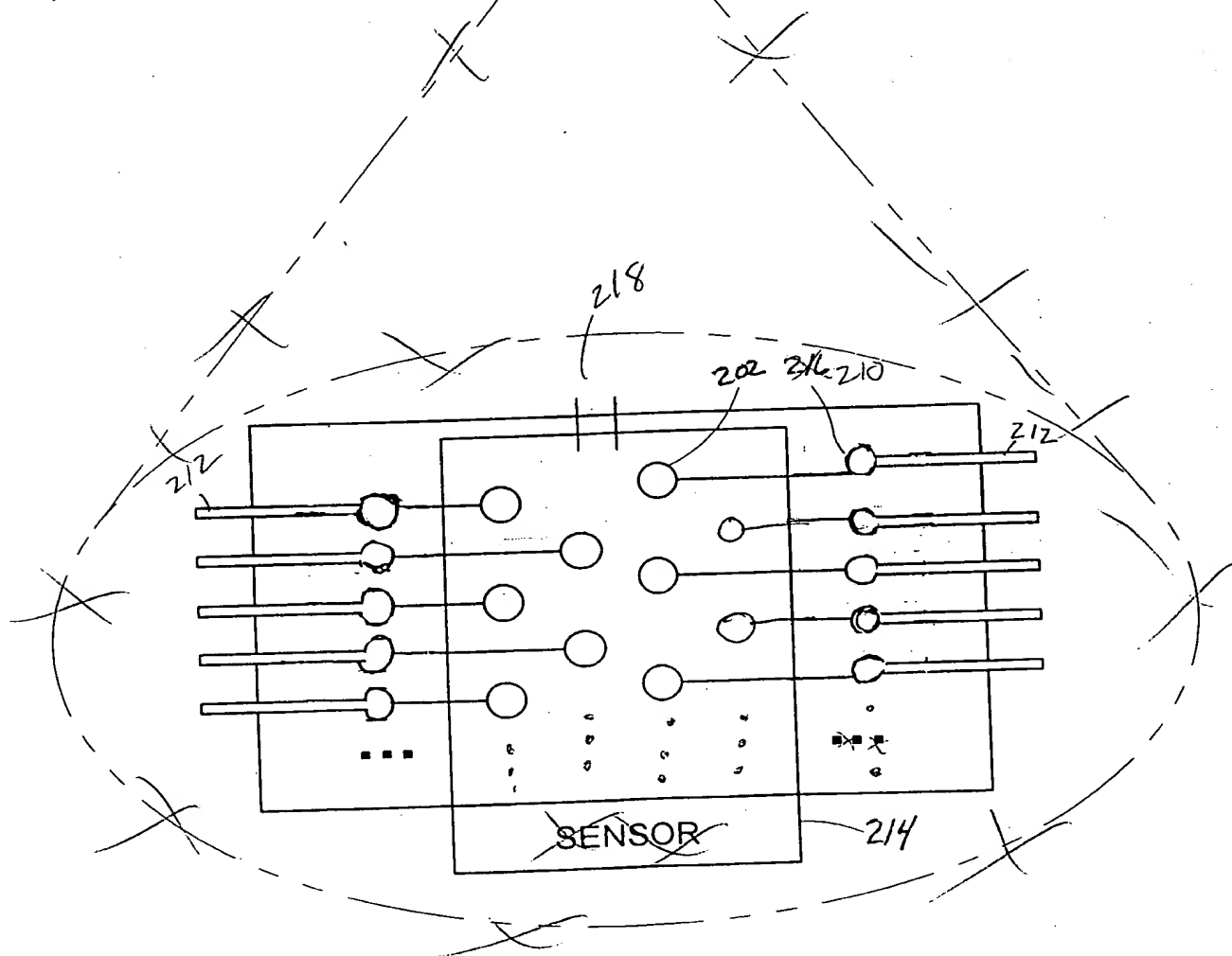
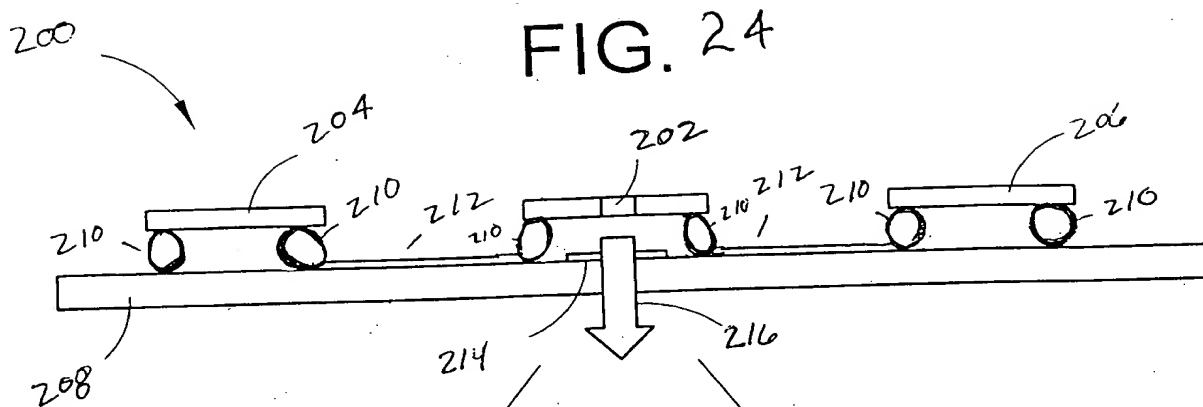


FIG. 22b



099440.08081

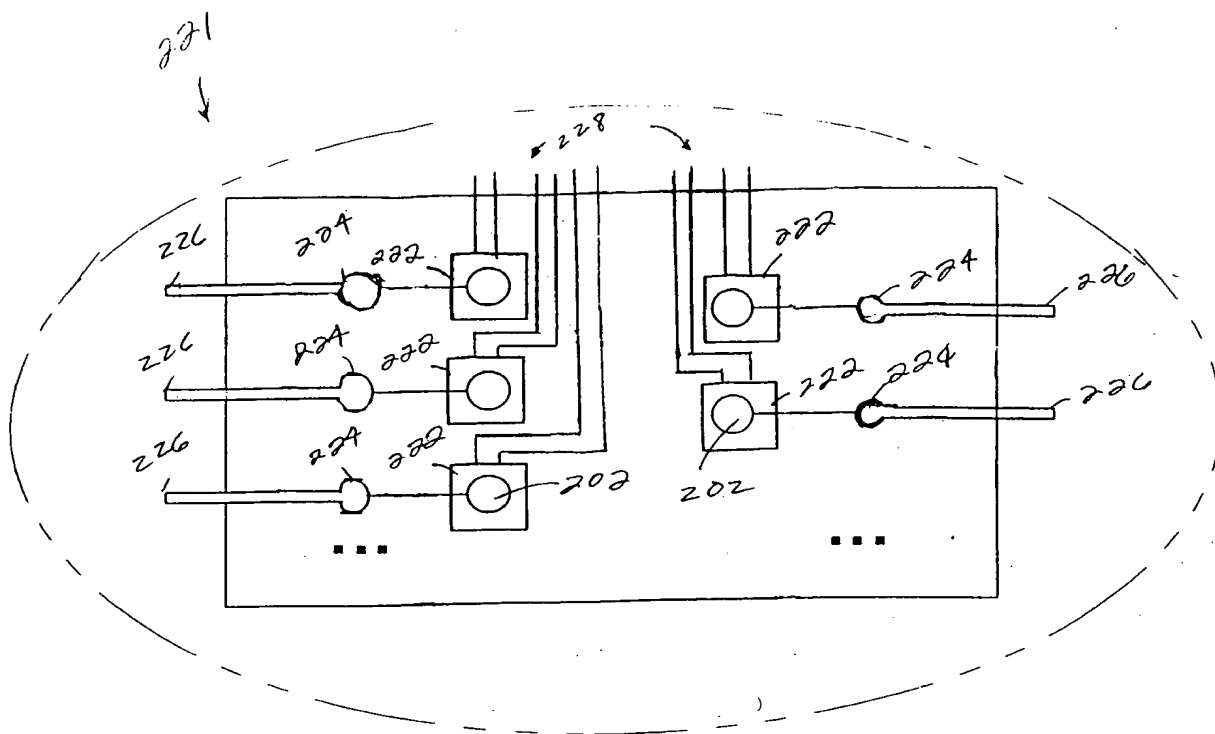


FIG. 26